

Xennia Amethyst Evo RC

**who can make a difference
with vibrant color and
outstanding fastness?**

you can.

working for you.



SunChemical®
a member of the DIC group 
Color & Comfort

Digital reactive technology delivering superior color & application performance

Sun Chemical brings digital reactive printing to the next level to Xennia Amethyst Evo RC, a new generation of reactive inks for industrial textile printers. Evolved from the pioneering Xennia Amethyst RC, this solution increases color strength and gamut, printer reliability and color efficiency. These optimized properties allow printers to maximize the performance of reactive prints.

Xennia Amethyst Evo is a high-quality, consistent ink that is specially formulated to enable more efficient production. This ensures volume customers meet their most demanding targets in fashion and home textiles without compromise.

Key performance benefits

- Maximized color strength
- Increased color gamut
- Balanced color for consistent print quality
- Increased dye fixation potential
- Batch to batch uniformity

Technology for a sustainable future

Working with customers to understand the pressures of high volume printing across a range of markets, we have developed a formulation and production process to deliver a solution that is simple to use and allows maximum printer uptime whilst at the same time increasing color performance - innovation you expect from Sun Chemical.

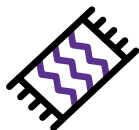
Available colors



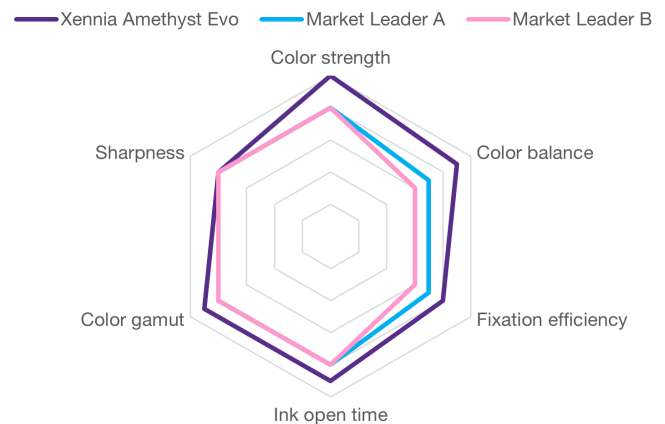
Applications



Fashion apparel



Interior textiles



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